

**Notice of References Cited**

Application/Control No.

10/566,194

Applicant(s)/Patent Under

Reexamination

RAS ET AL.

Examiner

DAVID TUROCY

Art Unit

1792

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,090,969	02-1992	Oki et al.	51/295
*	B	US-5,611,828	03-1997	Celikkaya, Ahmet	51/309
*	C	US-6,524,357	02-2003	Baldoni et al.	51/297
*	D	US-1,897,214	02-1933	RONALD RIDGWAY RAYMOND	423/291
*	E	US-2,356,938	08-1944	LOMBARD ROBERT H	51/307
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
*	N	ZA 200107995 A	07-2002	South Africa	HERING N et al.	
*	O	JP 09142932 A	06-1997	Japan	SUMIYA et al.	
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kim et al. Chemical vapor deposition of boron and boron nitride from decaborane (14), J. Vac. Sci. Technol. A 9 (4), Jul/Aug 1989, pages 2796-2799.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.